



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ilya Perlov et al. Art Unit : 3724
 Serial No. : 09/507,172 Examiner : Timothy V. Eley
 Filed : February 18, 2000
 Title : CHEMICAL MECHANICAL POLISHING SYSTEM HAVING MULTIPLE
 POLISHING STATIONS AND PROVIDING RELATIVE LINEAR MOTION

Commissioner for Patents
 Washington, D.C. 20231

RESPONSE

In response to the action mailed May 9, 2002, please amend the application as follows:

In the claims:

Please amend the claims to read as follows:

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1. (Amended Twice) A polishing apparatus, comprising: TECHNOLOGY CENTER R3700
 a rotatable support member rotatable about a first axis;
 at least two polishing surfaces arranged at respective angular positions about said first axis;
 at least one substrate head assembly supported on said rotatable support member and capable of supporting thereon a substrate in contact with a selected one of said polishing surfaces and affording relative linear and reciprocal movement between said selected polishing surface and said substrate head assembly while said substrate supported on said substrate head assembly is engaged with said selected polishing surface;
 wherein said at least one substrate head assembly is linearly and reciprocally movable in said rotatable support member.

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

September 9, 2002

Date of Deposit

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